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\*001\* 018; P0226 P0282-R D01 D18 F30; S9999 S1627 S1605; M9999 M2095-R;  
L9999 L2391; L9999 L2095-R; K9790-R; K9847-R K9790  
\*002\* 018; ND01; ND07; Q9999 Q8684 Q8673 Q8606; Q9999 Q6791; B9999 B5094  
B4977 B4740; B9999 B5652 B3521 B3510 B3372; N9999 N6837 N6655;  
K9585 K9483; K9610 K9483; Q9999 Q7476 Q7330; B9999 B4386 B4240  
\*003\* 018; R01066 G2335 D00 F20 C- 4A O- 6A; A999 A475; K9665; K9905;  
B9999 B4466-R  
\*004\* 018; D01 D11 D10 D50 D63 D85 F27 F26 F89 F41; A999 A475  
\*005\* 018; D01 D11 D10 D50 D63 D87 F34 F89 F41; A999 A475  
\*006\* 018; D01 D19 D18 D33 D76 D50 D61-R D93 B- 3A S- 6A; A999 A204  
\*007\* 018; D01 D11 D10 D23 D22 D31 D76 D45 D50 D89 D86 F19 Cl 7A; A999  
A204  
\*008\* 018; D01 D11 D10 D19 D18 D31 D76 D50 D63 D89 F89 F41 F75; A999 A204  
\*009\* 018; D01 D11 D10 D19 D18 D50 D94 F33 F30; A999 A793  
\*010\* 018; D01 D11 D10 D19 D18 D33 D76 D50 D94 F32 F30; A999 A793

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Rinsing method for photoresist - freezing rinsing liq. by applying  
liquefied carbon dioxide gas and then removing rinse liquid exposing  
resist

Patent Assignee: KAWASAKI STEEL CORP (KAWI )

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Patent Family:

| Patent No  | Kind | Date     | Applicat No | Kind | Date     | Main IPC     | Week     |
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Priority Applications (No Kind Date): JP 93158928 A 19930629

Patent Details:

| Patent     | Kind | Lan | Pg | Filing Notes | Application | Patent |
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Abstract (Basic): JP 7142333 A

The rinsing method involves flushing of development liquid which formed a resist (3) exposed by a predetermined pattern with rinsing liquid . Liquefied carbon dioxide (6) and applied over the rinsing liquid on the resist formed over a substrate (1) separated by a thin film (2). The liquefied carbon dioxide is cooled and freezes the rinsing liquid which is then removed by exposing the resist.

ADVANTAGE - Prevents collapsing of resists pillars which have high aspect ratio withstanding effect of surface tensile force.

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Title Terms: RINSE; METHOD; PHOTORESIST ; FREEZE; RINSE; LIQUID; APPLY;  
LIQUEFY; CARBON; DI; OXIDE; GAS; REMOVE; RINSE; LIQUID; EXPOSE; RESIST